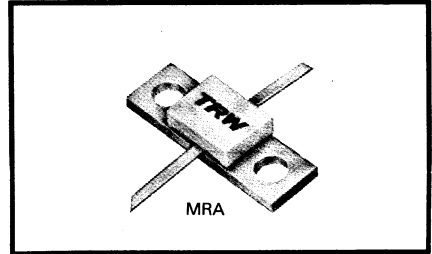


# MICroAMP

- 2-6-11-25 W
- Broadband 1400-1700 MHz
- Internally Compensated\*
- Gold Metalized
- Diffused Ballast Resistors
- MTTF Data



**Electrical Characteristics at  $T_{flange} = 25\text{ }^{\circ}\text{C}$**

Symbol	Characteristic	MRA1417-2	MRA1417-6	MRA1417-11	MRA1417-25
$BV_{CER}$	Collector-Base Breakdown Voltage $R_{BE} = 10\ \Omega$	$I_C = 20\text{ mA}$ 50 V Min	$I_C = 40\text{ mA}$ 50 V Min	$I_C = 80\text{ mA}$ 50 V Min	$I_C = 160\text{ mA}$ 50 V Min
$BV_{EBO}$	Emitter-Base Breakdown Voltage	$I_E = 0.25\text{ mA}$ 3.5 V Min	$I_E = 0.5\text{ mA}$ 3.5 V Min	$I_E = 1.0\text{ mA}$ 3.5 V Min	$I_E = 2.0\text{ mA}$ 3.5 V Min
$I_{CBO}$	Collector Cutoff Current $I_E = 0$	$V_{CB} = 28\text{ V}$ 0.5 mA	$V_{CB} = 28\text{ V}$ 1.0 mA	$V_{CB} = 28\text{ V}$ 2.0 mA	$V_{CB} = 28\text{ V}$ 4.0 mA
		$V_{CB} = 45\text{ V}$ 1.0 mA	$V_{CB} = 45\text{ V}$ 2.0 mA	$V_{CB} = 45\text{ V}$ 4.0 mA	$V_{CB} = 45\text{ V}$ 8.0 mA
$I_C$	Max Continuous Collector Current $V_{CE} = 4\text{ V}$	0.5 A	1.0 A	4.0 A	8.0 A
$h_{FE}$	Forward Current Transfer Ratio $V_{CE} = 5\text{ V}$	$I_C = 0.1\text{ A}$ 10-100	$I_C = 0.2\text{ A}$ 10-100	$I_C = 0.4\text{ A}$ 10-100	$I_C = 0.8\text{ A}$ 10-100
$\theta_{JF}$	Thermal Resistance Junction to Flange	15 $^{\circ}\text{C/W}$	8 $^{\circ}\text{C/W}$	4.5 $^{\circ}\text{C/W}$	2.5 $^{\circ}\text{C/W}$
$P_o$	Min Broadband Power Output	2.0 W	6.0 W	11.0 W	25.0 W
$C_{ob}$	Max Collector-Base Capacitance $V_{CB} = 28\text{ V}$ , $f = 1\text{ MHz}$	4.5 pF	8 pF	12 pF	24 pF
$P_{G(dB)}$	Min Power Gain in dB $V_{CB} = 28\text{ V}$	$P_o = 2.0\text{ W}$ 8.0 dB	$P_o = 6.0\text{ W}$ 7.4 dB	$P_o = 11.0\text{ W}$ 7.4 dB	$P_o = 25.0\text{ W}$ 7.0 dB
$\eta_c$	Min Broadband Collector Efficiency	$P_o = 2.0\text{ W}$ 40 %	$P_o = 6.0\text{ W}$ 45 %	$P_o = 11.0\text{ W}$ 45 %	$P_o = 25.0\text{ W}$ 45 %
$T_J$ & $T_{STG}$	Maximum Junction and Storage Temperatures : - 65 to + 200 $^{\circ}\text{C}$				

\* Based on Black's Equation and using  $\phi = 0.96\text{ eV}$ ,  $\beta = 1.07 \times 10^{-12}$  for unpassivated  $A_u$ . Empirical data indicates a 3-10 times improvement for glass passivated units. These units are glass passivated.

\* The concept of input and/or output matching using MOS capacitors, wire bonds and other techniques is patented by TRW, Inc. (US # 3,713,006).

The TRW MRA1417 series offers a complete family of broadband, high-gain transistors for applications in the 1.4-1.7GHz band.

Using internal compensation (a patented\* technique developed and first offered for sale by TRW), the MRA1417 series is intended for use in a variety of military and industrial applications including ECM, radio relay and telemetry.

The smooth, broadband transfer characteristics of the MRA1417 series makes it attractive for semi-linear applications without the need for bias. Power leveling within a broad range can be accomplished simply through control of low-level drive, thus eliminating brute force control of collector voltage.

Device output power levels of 2, 6, 11 and 25 watts allow a wide choice of lineup configurations. Excellent device-to-device phase tracking characteristics permit hybrid combination for higher powers with negligible combining loss.

Complete data and broadband circuitry, suitable to photograph for circuit boards, are contained herein.

#### DIFFUSED BALLASTING AND RELIABILITY

Microwave transistor devices are universally constructed using multiple cell combinations for higher power. A number of advantages are obtained using the cellular concept including better thermal balance and the ability to adjust power output capability using more or less cells to construct a device. Unless proper ballasting techniques are employed, some difficulty can be encountered in the act of combining cells. Ballasting makes cell combining practical. The alternative to ballasted cells is an operator-dependent assembly technique called "contour-bonding." Herein, bond wires of varying lengths are employed to adjust inductance and thereby achieve the expected balance. TRW has decided in favor of ballasting rather than contour-bonding because it is a controlled, repeatable and totally reliable technique.

While ballasting is desirable, certain techniques for creating ballast resistors in fine geometry microwave transistors have proven unreliable. Such an example is "metal" ballast resistors. Such resistors are incorporated by introducing an exposed section of barrier metal between the emitter finger and feeder bar. This type of resistor, of necessity, lies on top of an oxide layer. Because the metal resistor is required to dissipate as much as 10KW/CM<sup>2</sup>, extreme temperatures are generated in the resistor material. With this construction there is no adequate means of removing heat from the metal resistor. Therefore, the ballast resistor undergoes radical changes in physical dimension during its operating profile. This results in separation from the oxide layer or micro-cracking, or both.

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unattractive activation energy. Activation energy has an exponential relationship to metal migration.

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Junction Temperature	Times Improvement of MTTF with Gold vs Aluminum
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Note that all components of the input impedance are in parallel, which compounds the "Q" and bandwidth problem as more cells are used to achieve power, or the operating frequency is raised (or both). Figure 2 illustrates a more acceptable solution which combines inputs after an impedance transformation at the input of each device cell. It is convenient to do this all or partially within the package.

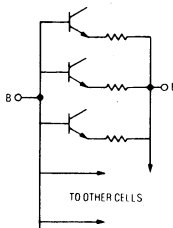


Figure 1. Elementary Method of Cell Combining

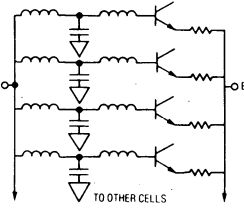


Figure 2. Cells Combined with Transformers

Correct input circuitry design can yield a device which is broadbandable over a broad range of frequencies (40 percent or more).

Because of the nature of source impedance driving the transistor cell (essentially a voltage source), as much as 10dB additional usable dynamic range without noticeably altering bandwidth or tuning is possible with the MICRoAMP.

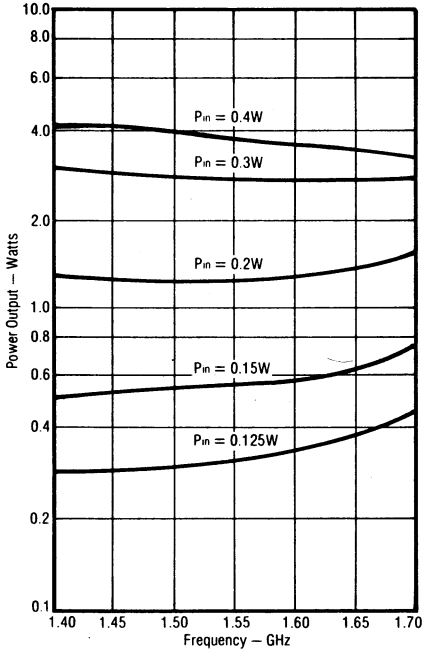
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\*TRW U.S. Patent #3,713,006

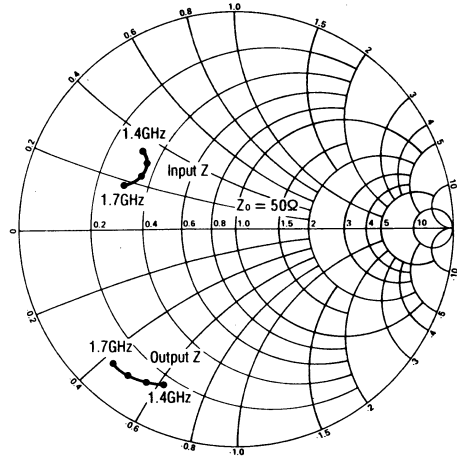


MRA1417-2 — 2 WATTS BROADBAND

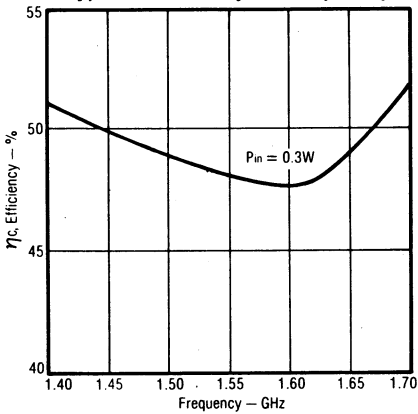
Typical Power Output vs Frequency



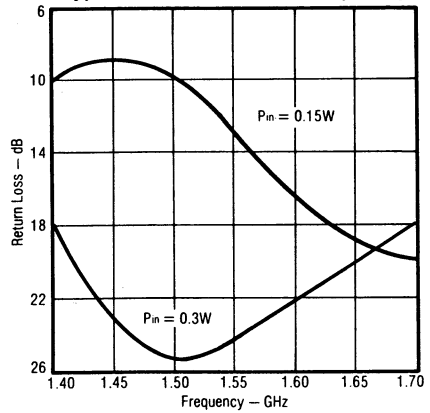
Impedance Data  
 $V_{cc} = 28V$



Typical Efficiency vs Frequency

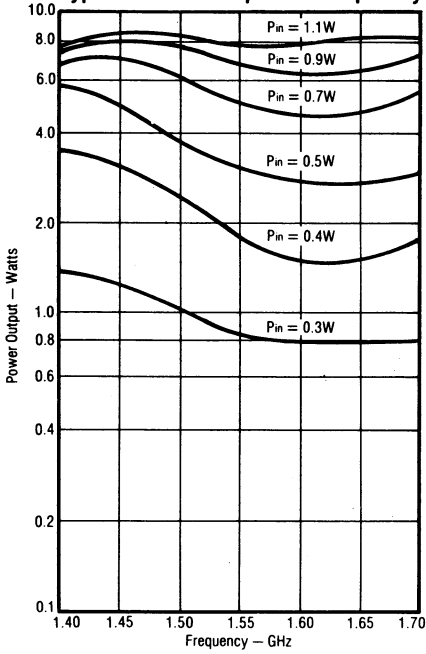


Typical Return Loss vs Frequency

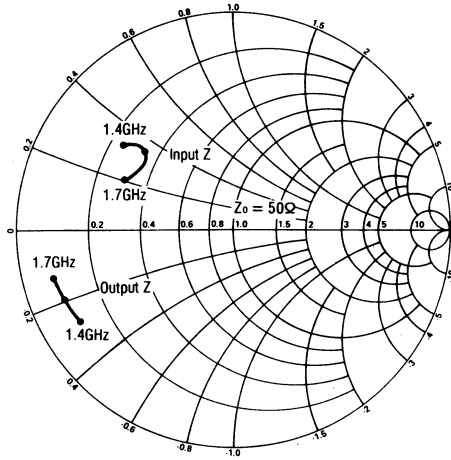


MRA1417-6 — 6 WATTS BROADBAND

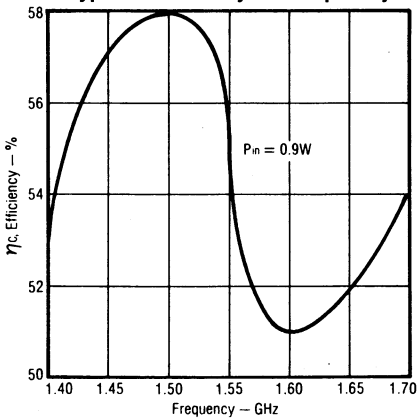
Typical Power Output vs Frequency



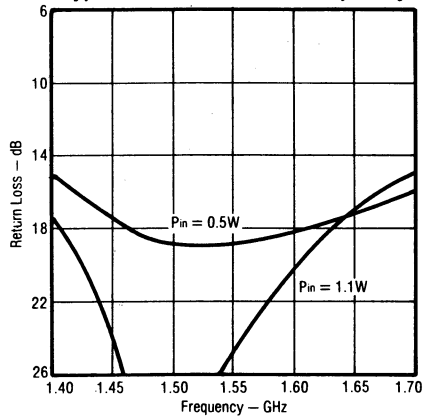
Impedance Data  
Vcc = 28V



Typical Efficiency vs Frequency

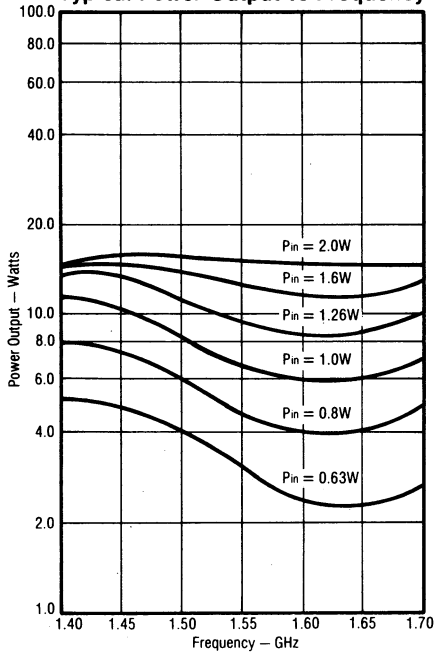


Typical Return Loss vs Frequency

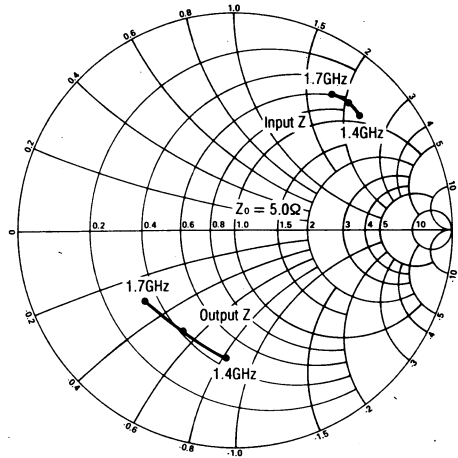


MRA1417-11 — 11 WATTS BROADBAND

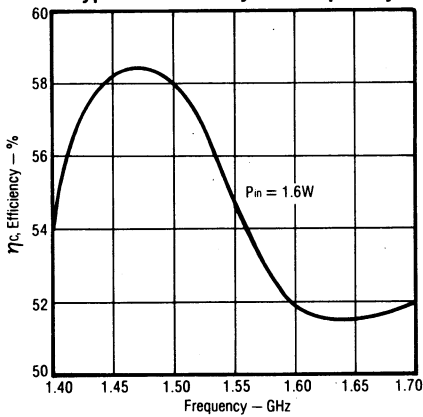
Typical Power Output vs Frequency



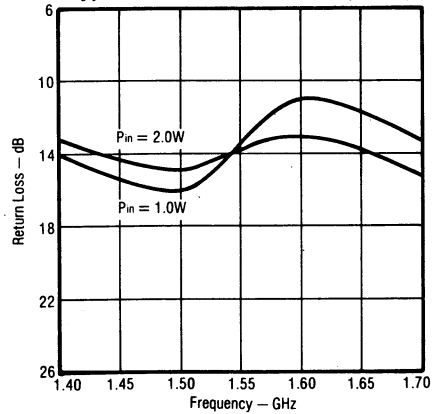
Impedance Data  
 $V_{CC} = 28V$



Typical Efficiency vs Frequency

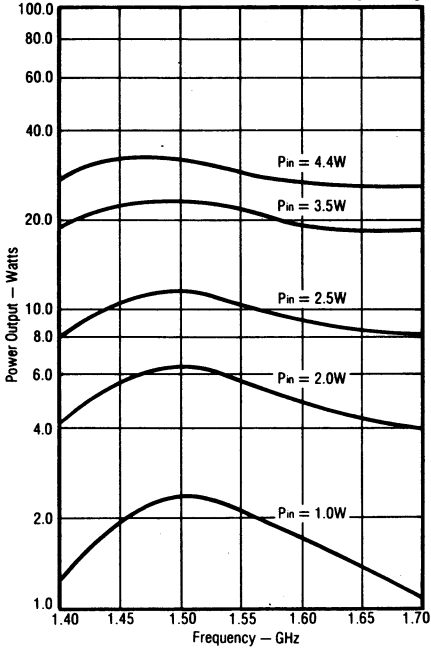


Typical Return Loss vs Frequency



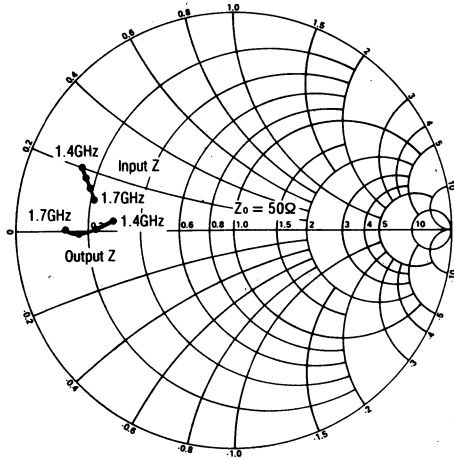
MRA1417-25 — 25 WATTS BROADBAND

Typical Power Output vs Frequency

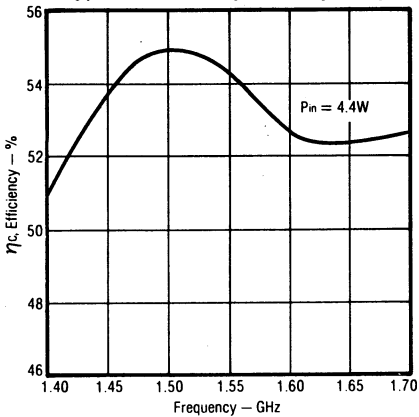


Impedance Data

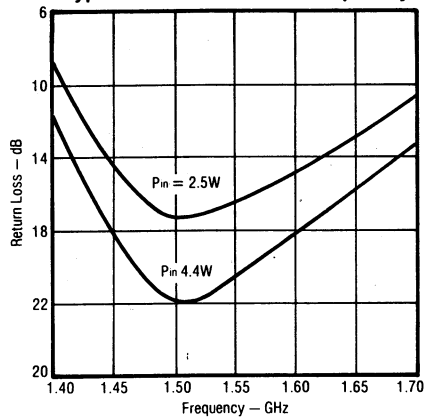
$V_{cc} = 28V$



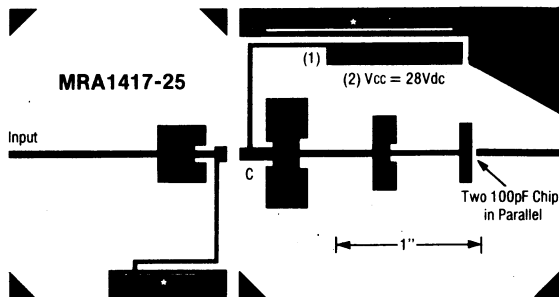
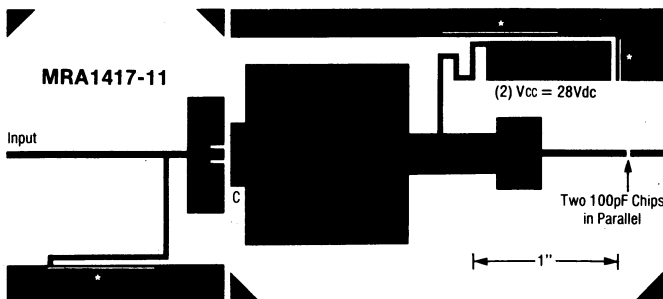
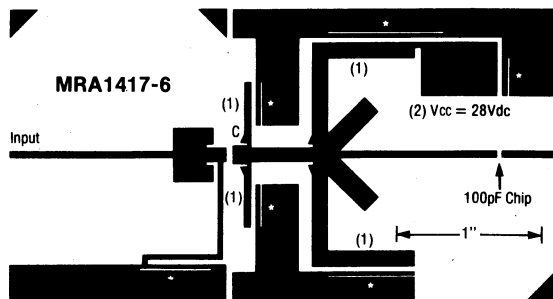
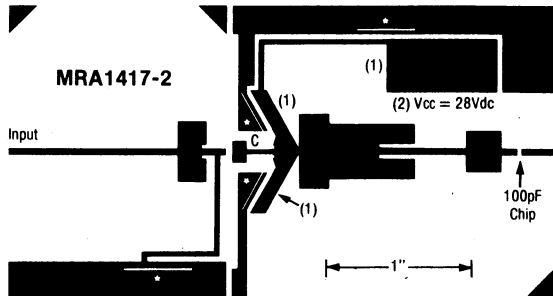
Typical Efficiency vs Frequency



Typical Return Loss vs Frequency



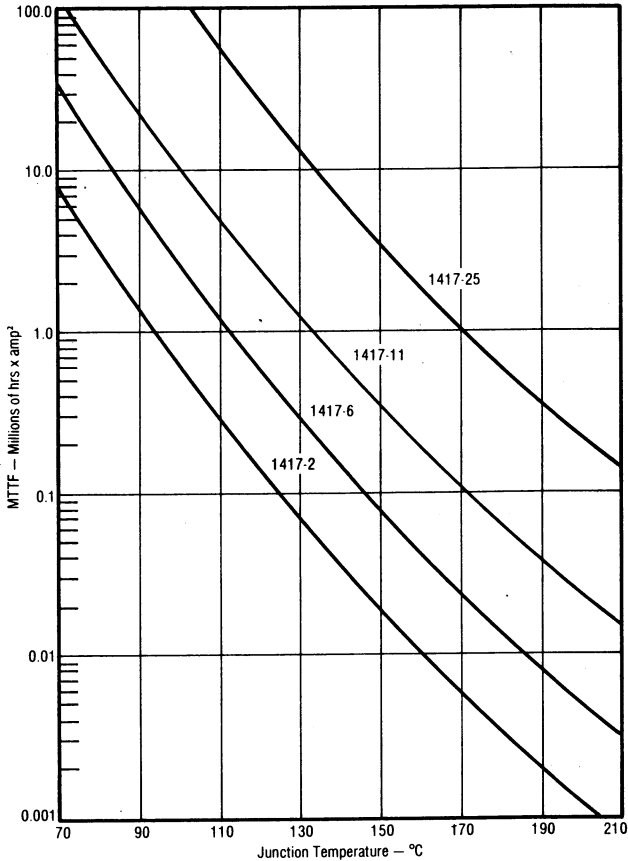
TEST CIRCUIT BOARDS FOR MRA1417 SERIES



\*Foil wrap or plate around to ground plane.  
 (1) Bypass capacitor to ground (220pF chip).  
 (2) Use Vcc bypass of 220pF chip, 0.1μF chip and 5μF.  
 Board material 0.020 inch glass-terlon Er = 2.55.

**MTTF FACTOR (Normalized to 1 Ampere<sup>2</sup> Continuous Duty)**

The graph shown below displays MTTF in hours x ampere<sup>2</sup> emitter current for each of the devices. Life tests at elevated temperatures have correlated to better than ±10% to the theoretical prediction for metal failure. Sample MTTF calculations based on operating conditions are included below.



**Example of MTTF for MRA1417-11 Conditions**

where:

- $P_o = 11W$
- $P_{in} = 2W$
- $V_{cc} = 28V$
- $\eta_c = 45\%$
- $T_{\text{flange}} = 70^\circ C$

$$I_c \cong I_E = \frac{P_o}{\eta_c \times V_{cc}} = 0.873A$$

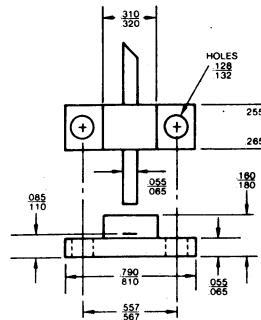
$$P_{diss} = P_{in} + V_{cc} I_c - P_o = 15.4W$$

$$T_{junc} = T_{\text{flange}} + \theta_f \times P_{diss} = 132^\circ C$$

$$MTTF = \frac{1.1 \times 10^6 \text{ hrs amp}^2}{I_c^2} = 1,443,328 \text{ hrs}$$

$$= 164 \text{ yrs}$$

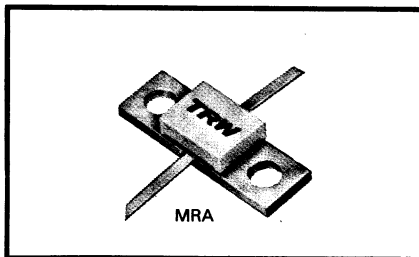
**MRA Series Package**





# MICroAMP

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- Broadband 1700-2000 MHz
- Internally Compensated\*
- Gold Metalized
- Diffused Ballast Resistors
- MTF Data



**Electrical Characteristics at  $T_{flange} = 25\text{ }^{\circ}\text{C}$**

Symbol	Characteristic	MRA1720-2	MRA1720-5	MRA1720-9	MRA1720-20
$BV_{CER}$	Collector-Base Breakdown Voltage $R_{BE} = 10\ \Omega$	$I_C = 20\text{ mA}$ 50 V Min	$I_C = 40\text{ mA}$ 50 V Min	$I_C = 80\text{ mA}$ 50 V Min	$I_C = 160\text{ mA}$ 50 V Min
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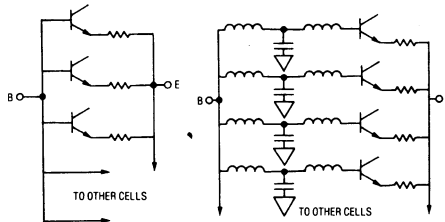


Figure 1. Elementary Method of Cell Combining

Figure 2. Cells Combined with Transformers

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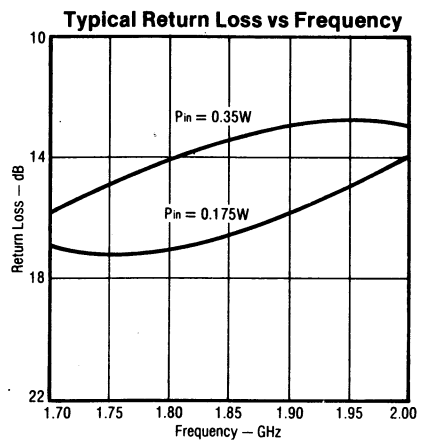
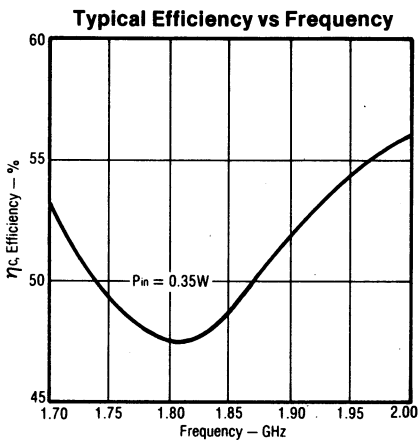
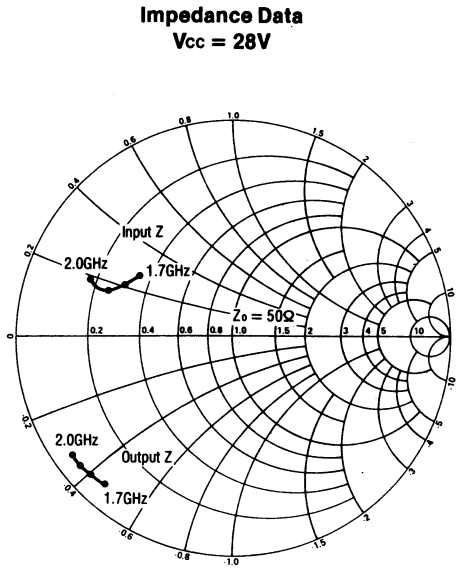
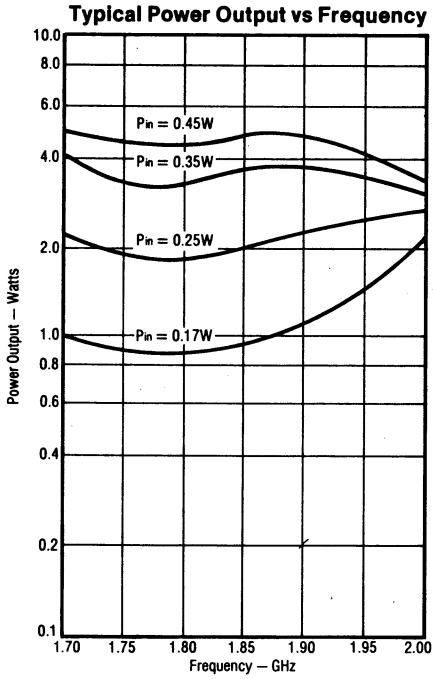
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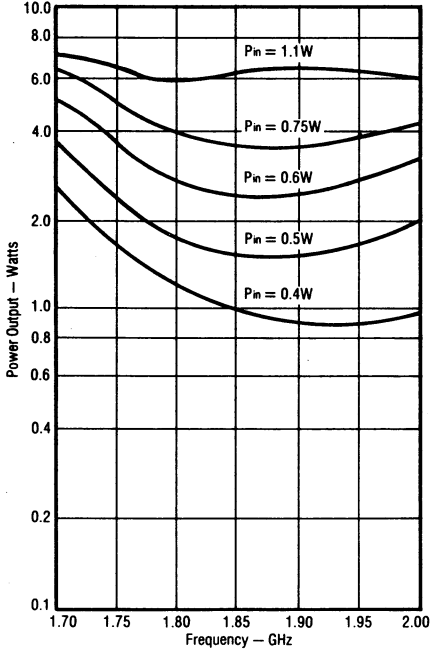


MRA 1720-2 WATTS BROADBAND

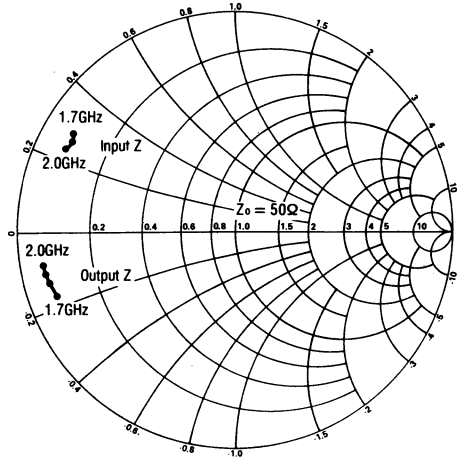


MRA 1720-5 — 5 WATTS BROADBAND

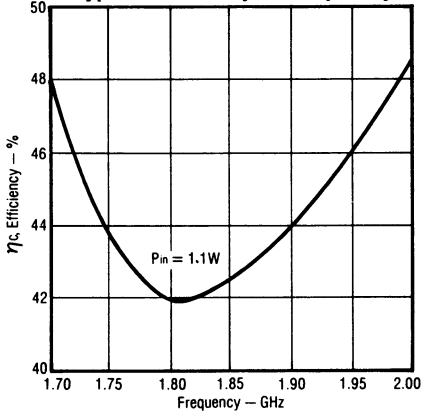
Typical Power Output vs Frequency



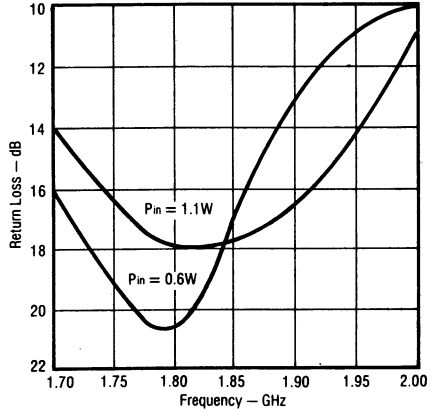
Impedance Data  
 $V_{CC} = 28V$



Typical Efficiency vs Frequency

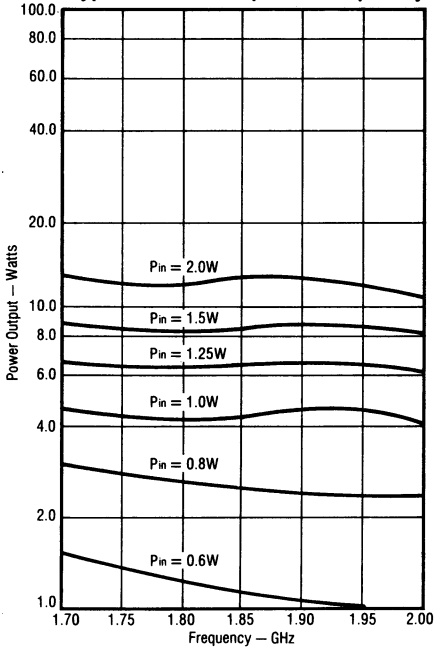


Typical Return Loss vs Frequency

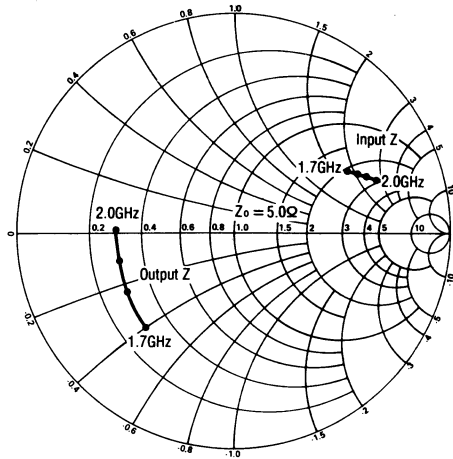


MRA 1720-9 — 9 WATTS BROADBAND

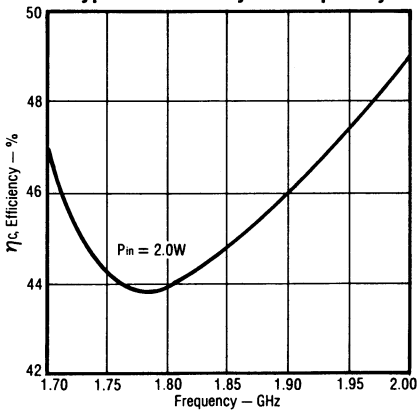
Typical Power Output vs Frequency



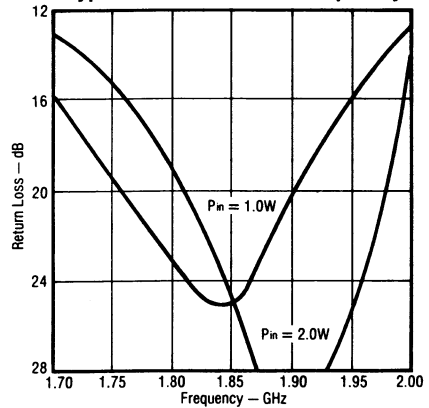
Impedance Data  
 $V_{CC} = 28V$



Typical Efficiency vs Frequency

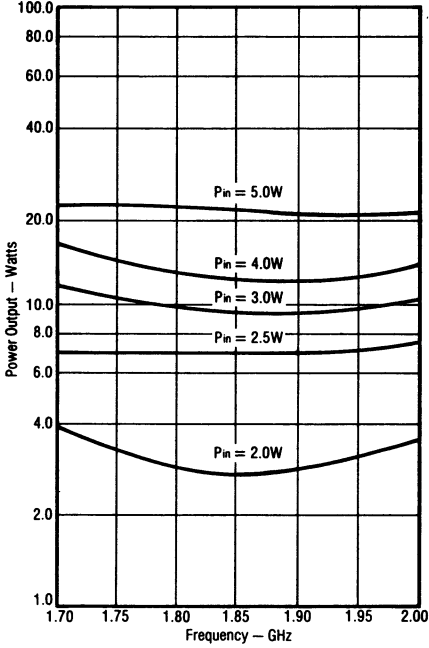


Typical Return Loss vs Frequency

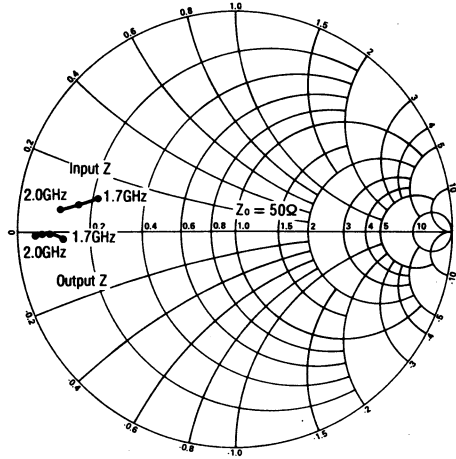


MRA 1720-20 — 20 WATTS BROADBAND

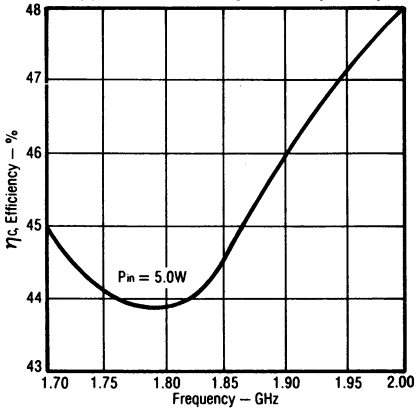
Typical Power Output vs Frequency



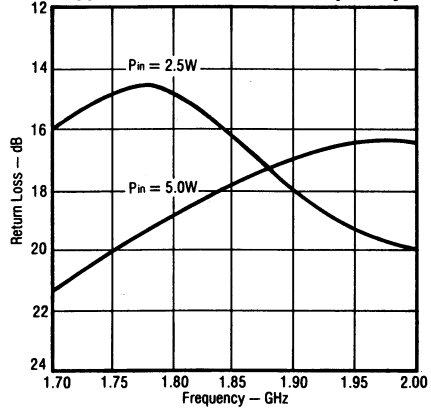
Impedance Data  
 $V_{CC} = 28V$



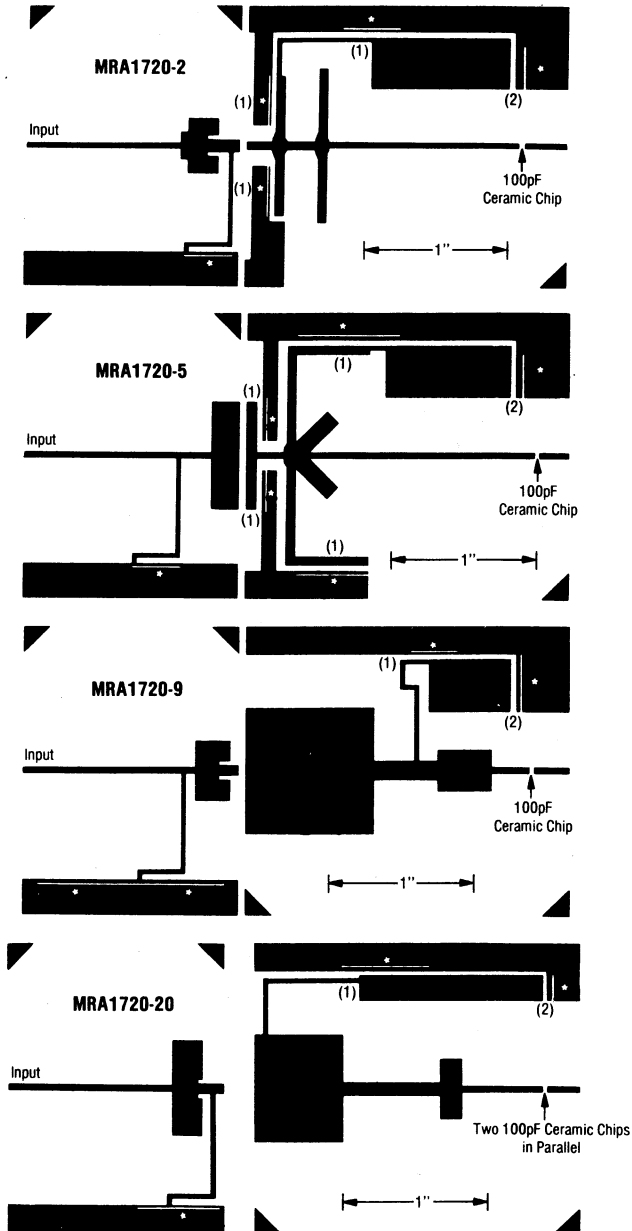
Typical Efficiency vs Frequency



Typical Return Loss vs Frequency



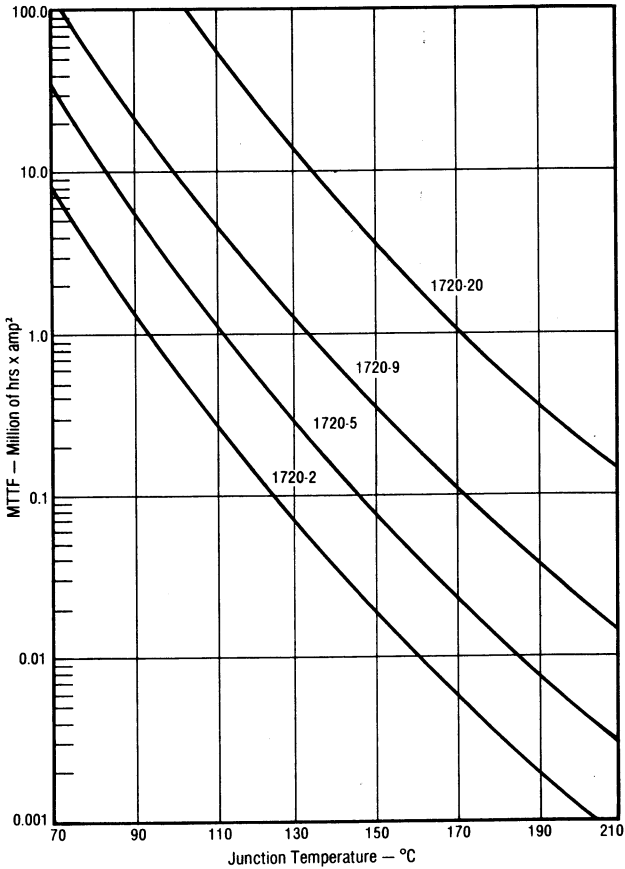
TEST CIRCUIT BOARDS FOR MRA1720 SERIES



\*Foil wrap or plate around to ground plane.  
 (1) Bypass capacitor to ground (100pF ceramic chip).  
 (2) Use Vcc bypass of 100pF chip, 0.1μF chip and 5μF.  
 Board material 0.020 inch glass-tyeflon  $\epsilon_r = 2.55$ .

**MTTF FACTOR (Normalized to 1 Ampere<sup>2</sup> Continuous Duty)**

The graph shown below displays MTTF in hours x ampere<sup>2</sup> emitter current for each of the devices. Life tests at elevated temperatures have correlated to better than ±10% to the theoretical prediction for metal failure. Sample MTTF calculations based on operating conditions are included below.



**Example of MTTF for MRA1720-9 Conditions**

where:

$P_o = 9W$

$P_{in} = 2W$

$V_{cc} = 28V$

$\eta_c = 40\%$

$T_{flange} = 70^\circ C$

$$I_c \cong I_E = \frac{100 P_o}{\eta_c \times V_{cc}} = 0.800A$$

$P_{diss} = P_{in} + V_{cc} I_c - P_o = 15.4W$

$T_{junc} = T_{flange} + \theta_F \times P_{diss} = 139.3^\circ C$

$$MTTF = \frac{0.7 \times 10^5 \text{ hrs amp}^2}{I_c^2} = 109,380 \text{ hrs}$$

$$= 12.46 \text{ yrs}$$

**MRA Series Package**

